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Laser-based Micro- and Nanoprocessing XIV

**Udo Klotzbach
Akira Watanabe
Rainer Kling**
Editors

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Contents

vii *Authors*
ix *Conference Committee*

SESSION 1 MICROFLUIDICS AND MEDICAL MICRO SYSTEMS: JOINT SESSION WITH 11235 AND 11268

- 11268 02 **Recent advances in 3D printing of pure proteinaceous microstructures by femtosecond laser direct write (Invited Paper) [11268-1]**
- 11268 04 **Laser-induced cell injury in closed micro physiological systems: a novel method to study regeneration processes in vitro [11268-81]**
- 11268 06 **Biological analysis in 3D optofluidic devices fabricated by femtosecond laser micromachining (Invited Paper) [11268-4]**
- 11268 07 **Effects of the dissolved gases in water on microbubble oscillation under photothermal heating [11268-5]**

SESSION 2 LASER MICRO STRUCTURING AND PROCESSING

- 11268 08 **Three-dimensional laser printing of macro-scale glass objects at a micro-scale resolution [11268-6]**
- 11268 09 **Enhanced ablation using GHz-pulsed fs laser (Invited Paper) [11268-7]**
- 11268 0B **Surface treatment with GHz bursts [11268-9]**
- 11268 0D **Sub-diffraction direct laser writing by a combination of STED and ESA [11268-11]**
- 11268 0E **Femtosecond laser induced ablation dynamics probing by emission and scattering spectroscopy under various vacuum conditions [11268-12]**

SESSION 3 LASER MICRO/NANO PROCESSING ON TRANSPARENT MATERIAL I

- 11268 0F **Advances in transparent materials processing by ultrashort laser pulses (Invited Paper) [11268-13]**
- 11268 0G **Laser-based manufacturing of 2.5D bodies of polylactide (Invited Paper) [11268-14]**
- 11268 0H **Laser process of transparent conducting surfaces for terahertz bandpass ultrathin metamaterials [11268-15]**

SESSION 4 LASER MICRO/NANO PROCESSING ON TRANSPARENT MATERIAL II

- 11268 OK **Patterning of transparent polymers using high-throughput methods: application in flexible perovskite solar cells with enhanced light trapping** [11268-18]
- 11268 OL **Ablation of amorphous Polyethy(ethyl)etone (PEEK) by a femtosecond Ti:sapphire laser** [11268-19]
- 11268 ON **Photoinscription of optical microstructures in fused silica with few-cycle pulses** [11268-21]

SESSION 5 LASER MICRO/NANO PROCESSING ON METAL

- 11268 OO **Femtosecond laser induced micro/nano structures on metals** [11268-22]
- 11268 OP **Laser polishing using ultrashort pulse laser** [11268-23]
- 11268 OQ **Effect of process parameters on surface texture generated by laser polishing of additively manufactured Ti-6Al-4V** [11268-24]
- 11268 OR **Ultrashort-pulse laser micro-polishing of lithium niobate by using UV-ps pulses** [11268-25]

SESSION 6 LARGE AREA MICRO/NANOSTRUCTURING LASER INTERFERENCE PATTERNING I

- 11268 OS **Fabrication of versatile functional surface properties based on femtosecond laser-induced periodic surface structures (LIPSS) (Invited Paper)** [11268-26]
- 11268 OT **High-throughput direct laser interference patterning: new configurations and applications** [11268-28]
- 11268 OU **In-situ laser interference patterning of MBE growth surfaces** [11268-29]

SESSION 7 LARGE AREA MICRO/NANOSTRUCTURING LASER INTERFERENCE PATTERNING II

- 11268 OX **Improvement of metallic surfaces hydrophobicity and corrosion resistance by direct write and combined direct write-DLIP hierarchical micro-nano structuring (Invited Paper)** [11268-32]
- 11268 OY **How to improve throughput in direct laser interference patterning: top-hat beam profile and burst mode** [11268-33]
- 11268 OZ **Maximizing the efficiency of laser-fabricated diffraction gratings on PET using direct laser interference patterning** [11268-34]

11268 10 **Surface flattening of poly-Si thin films by laser annealing and electrical properties of LTPS-TFTs**
[11268-35]

SESSION 8 DIRECT WRITE PROCESSING ABLATION AND SURFACE MODIFICATION I

11268 12 **Biomechanical metamaterials fabricated through multiphoton lithography by tailoring 3D buckling (Invited Paper)** [11268-37]

11268 13 **Superior microstructures for advanced package integration** [11268-38]

SESSION 9 DIRECT WRITE PROCESSING ABLATION AND SURFACE MODIFICATION II

11268 16 **Laser processing of plasmonic metal oxides and phase change materials (Invited Paper)**
[11268-41]

11268 17 **Formation of graphene hybrid structures by laser direct writing and sensor applications**
[11268-42]

11268 18 **Impact of laser texturing parameters and processing environment in the anti-wetting transition of nanosecond laser generated textures** [11268-43]

11268 19 **Laser-based surface treatment of CFRP and aluminum for adhesively bonded hybrid joints**
[11268-44]

SESSION 10 BEAM SHAPING AND PROPAGATION FOR LASER MICRO/NANO PROCESSING

11268 1A **Nanograting based birefringent retardation elements in integrated photonic circuits** [11268-46]

11268 1B **Laser induced periodic surface structures generation by femtosecond laser and multi-plane light conversion beam shaping** [11268-47]

11268 1C **Efficiency improvement of multilayer lab-on-a-chip production by dynamic beam shaping**
[11268-48]

11268 1D **Realization of higher order vector Bessel beams for transparent material processing applications** [11268-50]

SESSION 11 HIGH SPEED LASER BEAM ENGINEERING SYSTEMS

11268 1F **Pulse to pulse control in micromachining with femtosecond lasers** [11268-52]

11268 1G **Divide-and-conquer laser beam deflection system: Fast, wide-ranging, and flexible** [11268-53]

11268 1H **Pump-probe imaging for process control and optimization in high-speed laser micro machining** [11268-54]

SESSION 12 DIRECT WRITE PROCESSING ABLATION AND SURFACE MODIFICATION III

11268 1J **The analysis of harmonic generation during ultrashort IR pulses filamentation in polymer** [11268-56]

11268 1L **Internal micro structuring of transparent optical polymers by fs laser** [11268-58]

11268 1M **Advanced sensors: Industry 4.0 for the laser microjet technology** [11268-59]

POSTER SESSION

11268 1O **Structuring of forming tools for lubricant-free deep drawing** [11268-27]

11268 1T **Comparative study between laser blasted and sandblasted surfaces of Ti₆Al₄V** [11268-63]

11268 1Y **Formation of optical needles by Pancharatnam-Berry phase element for laser-induced modifications in transparent materials** [11268-69]

11268 1Z **Smart ultra short pulse laser processing with rotating beam: laser micro drilling, cutting, and turning** [11268-70]

11268 22 **Metal enhanced fluorescence using nanostructures on silver formed with Ti: Sapphire femtosecond pulsed laser** [11268-73]

11268 24 **Hot embossing of multifunctional transparent polymers from Cr stamps structured by direct laser interference patterning** [11268-75]

11268 28 **Development of a complex laser processing system for cutting and drilling** [11268-79]

11268 29 **Absorption and photoluminescence of ZnSe quantum dots synthesized by femtosecond laser ablation in microfluidics** [11268-80]

Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Abate, Antonio, 0K
Aguilar, Alfredo I., 0T
Aguilar-Morales, A. I., 0X
Ahmed, Mohammad, 1T
Alamri, Sabri, 0T, 0X, 0Z
Alberucci, A., 1A
Allegre, Olivier, 0L
Aminuzzaman, Mohammad, 17
Angulo, I., 0X
Antończak, Arkadiusz J., 1J
Arnold, Mark, 0H
Audouard, E., 1F
Auyeung, Raymond C. Y., 16
Baltrukonis, Justas, 1D, 1Y
Bassi, Andrea, 06
Beer, S., 0F
Behrens, Stephan, 1C
Biaseffi, Demian, 0N
Bourtereau, A., 1F
Bragheri, Francesca, 06
Braunmüller, Falk, 1M
Brenner, A., 0P
Brosius, Alexander, 1O
Brune, J., 13
Budnicki, Aleksander, 1J
Cai, Jinguang, 17
Cardoso, J. T., 0X
Cavallini, Daniel, 22
Chalker, Paul, 0L
Charipar, Kristin M., 16
Charipar, Nicholas A., 16
Charles, A. P., 0Q
Chen, Jinn-Kuen, 0O
Cheng, Chung-Wei, 0O
Cheng, Ya, 08
Chu, Wei, 08
Cordovilla, F., 0X
de Castro Neto, Jarbas C., 22
De Silva, Anjali, 19
de Souza, Marco A. A., 22
Dearden, Geoff, 0L
Delaigue, M., 1F
Delmdahl, R., 13
Diboine, Jérémie, 1M
Ding, Hongtao, 0H
Du, Keming, 0Y
Düsing, Jan, 1G
Ebert, Robby, 0G
Edwardson, Stuart P., 0L
Ehrhardt, M., 1A
Elkaseer, A., 0Q
Engel, S., 0D
Engel, W. Dieter, 0N
Esen, Cemal, 1L
Exner, Horst, 0G
Farsari, Maria, 12
Faucon, M., 1B, 1F
Feng, Guoying, 29
Finger, J., 0P
Flamm, D., 0F
Förster, Deborah, 04
Fortuna, Franco, 24
Franke, Volker, 1C
Fu, Yangxi, 24
Furch, Federico J. A., 0N
Gao, Bingtao, 0H
García-Beltrán, A., 0X
Gertus, T., 1Y
Godoy Vilar, J. P., 18
Gooßen, Michael, 19
Góra, W. S., 18
Goto, Tetsuya, 10
Gotovski, Pavel, 1D, 1Y
Gräf, S., 0D, 0S
Grigoropoulos, Costas P., 0E, 12
Gross, H., 1A
Grossmann, D. G., 0F
Gu, Grace, 12
Guimarães, Francisco E. G., 22
Hamano, Fuminobu, 10
Han, Gyoowan, 0E
Han, Im Sik, 0U
Hand, D. P., 18
Harrison, David, 19
Hecker, S., 0F
Hellmann, Ralf, 1L
Hendow, Sami, 09
Hiroshige, Nao, 07
Ho, Janet, 0L
Hoenninger, C., 1F
Hohenstein, Bernd, 04
Hopkinson, Mark, 0U
Huerta-Murillo, D., 0X
Ikenoue, Hiroshi, 10
Imokawa, Kaname, 10
Jacquard, C., 1B
Jähnig, Theresa, 1O
Jäschke, Peter, 1G

Jenne, M., 0F
 Jeong, Seongho, 0E
 Jeun, Jinhong, 0E
 Jian, P., 1B
 Jin, Chao Yuan, 0U
 Jukna, Vytautas, 1D, 1Y
 Kaierle, Stefan, 1G
 Kaiser, M., 0F
 Kawano, Hiroyuki, 02
 Kim, Heungsoo, 16
 Kleiner, J., 0F
 Kling, R., 1B, 1F
 Klotzbach, Udo, 04, 1C
 Knoblauch, Voiker, 19
 Koch, Jürgen, 1G
 Komvopoulos, Kyriakos, 12
 Kraff, Sebastian, 1H
 Krupop, Benjamin, 0T
 Kumkar, M., 0F
 Kuntze, Thomas, 1C
 Kunz, C., 0S
 Kunze, Tim, 0T, 0Z
 Laborie, Hugo, 1F
 Labroille, G., 1B
 Lammers, K., 1A
 Lang, Valentin, 0K, 0T
 Laporte, Grégoire, 1M
 Lasagni, Andrés Fabián, 0K, 0T, 0X, 0Y, 0Z, 1O, 24
 Lee, Sunwoo, 28
 Lendner, Florian, 1Z
 L'huillier, Johannes, 0B, 0R
 Li, Qianliang, 0L
 Li, Xiaolong, 08
 Li, Zhaoqing, 0L
 Lim, Seokkyun, 28
 Lin, Zijie, 08
 Liu, Yi-Hsien, 0O
 Loeschner, Udo, 1H
 Ma, Zhen, 12
 Madelung, Aleksander, 0T
 Mattos, Vicente S., 22
 Mauersberger, Stefan, 1H
 Meinhard, Dieter, 19
 Memeo, Roberto, 06
 Mermillod-Blondin, Alexandre, 0N
 Michalowski, Andreas, 0B
 Mincuzzi, G., 1B, 1F
 Mishchik, K., 1F
 Miyawaki, Atsushi, 02
 Mizutani, Akira, 10
 Mousavi, Ali, 1O
 Müller, D., 13
 Müller, F. A., 0D, 0S
 Nacius, E., 1Y
 Nakamura, Daisuke, 10
 Namura, Kyoko, 07
 Nolte, S., 0F, 1A
 Nourry, S., 1B
 Nyenhuis, Fabian, 0B
 Ocaña, J. L., 0X
 Okai, Shunsuke, 07
 Orlov, Sergej, 1D, 1Y
 Osbild, M., 0P
 Osellame, Roberto, 06
 Overmeyer, Ludger, 1G
 Pabst, Linda, 0G
 Paiè, Petra, 06
 Pallier, G., 1B
 Paolillo, Fernanda R., 22
 Park, Hyeongchan, 28
 Park, Minok, 0E
 Pätzelt, R., 13
 Pereira-da-Silva, Marcelo A., 22
 Perez-Leija, Armando, 0N
 Perrie, Walter, 0L
 Pflöging, W., 0Q
 Pinel, O., 1B
 Piqué, Alberto, 16
 Rahman, Ashiqur, 17
 Rebière, A., 1F
 Richerzhagen, Bernold, 1M
 Riegel, Harald, 19
 Roh, Cheollae, 0E
 Rösler, Mechthild, 04
 Roth, Gian-Luca, 1L
 Röther, L., 0P
 Ryu, Kwanghyun, 28
 Sala, Federico, 06
 Schäfer, M., 0F
 Schäfer, Mareike, 0R
 Schanz, Jochen, 19
 Schille, Joerg, 1H
 Schmieder, Florian, 04, 1C
 Schneider, Lutz, 1H
 Schöps, Patrick, 1C
 See, Tian Long, 18, 1T
 Seifert, H. J., 0Q
 Serien, Daniela, 02
 Siems, M., 1A
 Šlevas, P., 1Y
 Soldera, Flavio, 0K
 Soldera, Marcos, 0K, 0Z, 24
 Solheid, J. S., 0Q
 Sonntag, Frank, 04, 1C
 Sradnick, Jan, 04
 Steege, Tobias, 0T
 Stępak, Bogusz D., 1J
 Storm, Sebastian, 0Z
 Ströbel, Joachim, 0Y
 Sugioka, Koji, 02
 Suzuki, Motofumi, 07
 Szameit, A., 1A
 Takahashi, Hidetomo, 09
 Tang, Yue, 0L
 Taschner, Patrick A., 1G
 Toor, Fatima, 0H
 Torchia, Gustavo, 0N

Ulcinas, Orestas, 1D, 1Y
Vangelatos, Zacharias, 12
Viertel, Tina, 0G
Voisiat, Bogdan, 0Y
Vrakking, Marc J. J., 0N
Wang, Peng, 08
Wang, Qinghua, 0H
Wang, Qiong, 0K
Wang, Wei, 24
Wang, Yun Ran, 0U
Watanabe, Akira, 17
Wenisch, C., 0D
Witting, Tobias, 0N
Wunsch, T., 0Q
Xu, Jian, 08
Xu, Jingzhou, 09
Yamaguchi, Mariko, 09
Yang, Chao, 29
Yasuoka, Fatima M. M., 22
Zhang, Haisu, 08
Zhang, Yuqin, 29
Zimmermann, F., 0F
Zryd, Amédée, 1M

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- 1 Microfluidics and Medical Micro Systems: Joint Session with 11235 and 11268
Holger Becker, microfluidic ChipShop GmbH (Germany)
Udo Klotzbach, Fraunhofer-Institut für Werkstoff- und Strahltechnik IWS (Germany)
- 2 Laser Micro Structuring and Processing
Udo Klotzbach, Fraunhofer-Institut für Werkstoff- und Strahltechnik IWS (Germany)
- 3 Laser Micro/Nano Processing on Transparent Material I
Akira Watanabe, Tohoku University (Japan)
- 4 Laser Micro/Nano Processing on Transparent Material II
Rainer Kling, ALPhANOV (France)
- 5 Laser Micro/Nano Processing on Metal
Kunihiko Washio, Paradigm Laser Research Ltd. (Japan)
- 6 Large Area Micro/Nanostructuring Laser Interference Patterning I
Andrés-Fabián Lasagni, TU Dresden (Germany)
- 7 Large Area Micro/Nanostructuring Laser Interference Patterning II
Yongfeng Lu, University of Nebraska-Lincoln (United States)
- 8 Direct Write Processing Ablation and Surface Modification I
Udo Klotzbach, Fraunhofer-Institut für Werkstoff- und Strahltechnik IWS (Germany))
- 9 Direct Write Processing Ablation and Surface Modification II
Ya Cheng, Shanghai Institute of Optics and Fine Mechanics, Chinese Academy of Sciences (China)

- 10 Beam Shaping and Propagation for Laser Micro/Nano Processing
Udo Klotzbach, Fraunhofer-Institut für Werkstoff- und Strahltechnik IWS
(Germany)
Rainer Kling, ALPhANOV (France)
- 11 High Speed Laser Beam Engineering Systems
Wilhelm Pfleging, Karlsruher Institut für Technologie (Germany)
- 12 Direct Write Processing Ablation and Surface Modification III
Arkadiusz J. Antonczak, Wrocław . Wrocław Wrocław University of
Science and Technology (Poland)

